

**EECS 16B**

# **Designing Information Devices and Systems II**

## **Lecture 9**

Prof. Sayeef Salahuddin

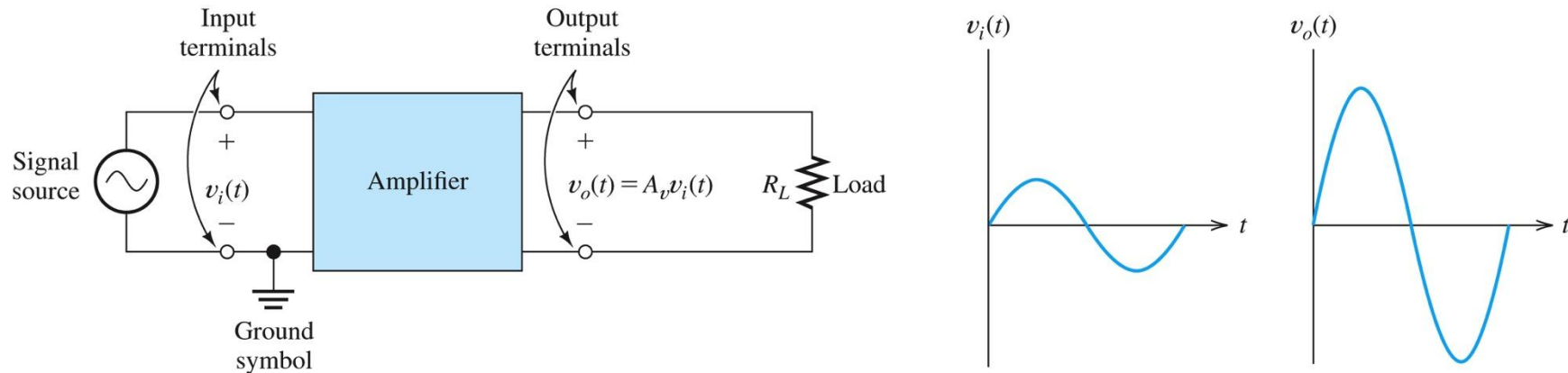
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# Devices

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- Outline
  - Amplifiers and Devices
- Reading-slides

# Active Devices



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- Active devices are made of semiconductors
- Semi-conductors are materials whose resistance is in between a metal and insulator

## Half

- More interestingly, one is able to change the resistance of the semiconductor materials by using external control such as voltage or current

# Semiconductors

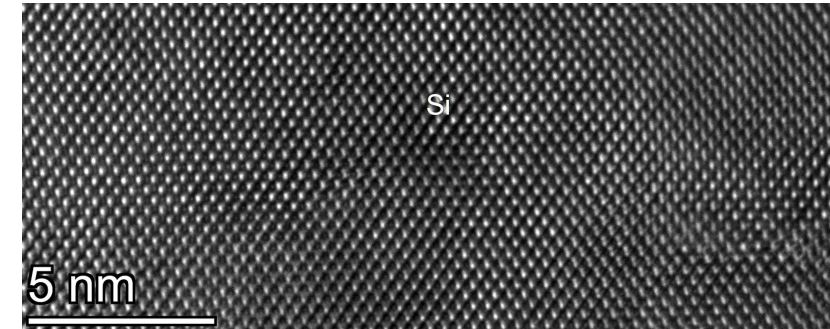
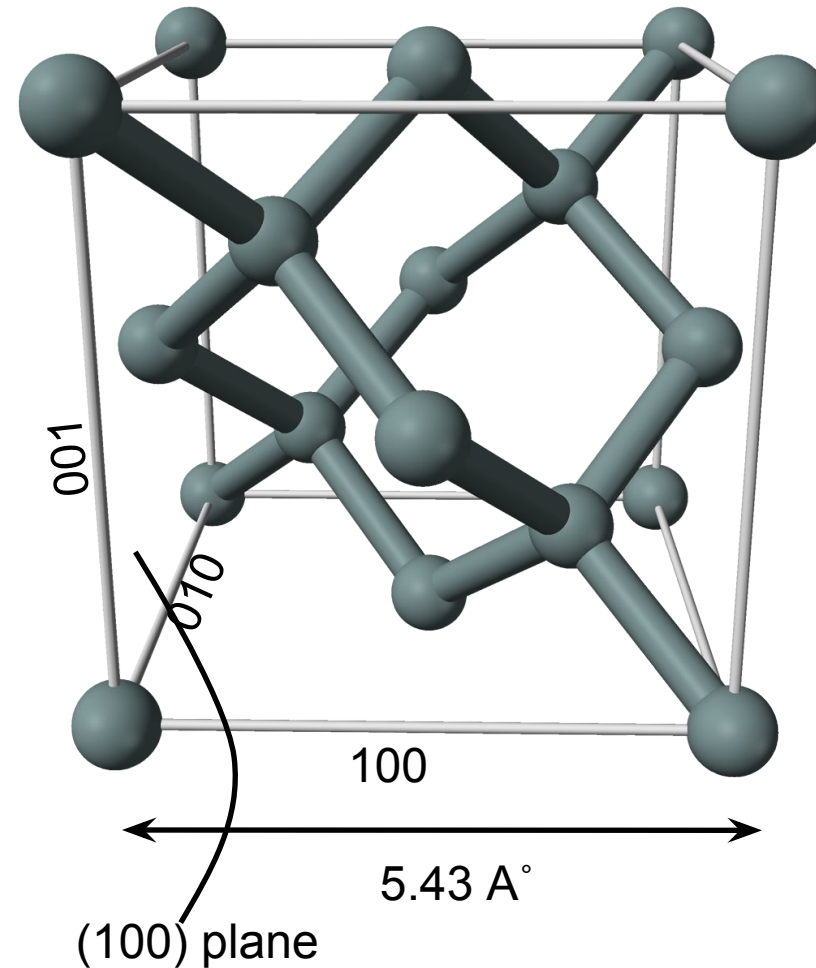
- Semiconductors are **usually** made of group IV elements- atoms that contain, on average, four valence electrons
- Most Common semiconductor used in electronic devices is **Silicon**

Periodic Table of the Elements

1	IA	1	H	2	IIA	3	Li	4	Be	5	III A	6	B	7	IV A	8	V A	9	VIA	10	VII A	11	He														
2		3	Li	4	Be								5	B	6	C	7	N	8	O	9	F	10	Ne													
3		11	Na	12	Mg	13	Al	14	Si	15	P	16	S	17	Cl	18	Ar																				
4		19	K	20	Ca	21	Sc	22	Ti	23	V	24	Cr	25	Mn	26	Fe	27	Co	28	Ni	29	Cu	30	Zn	31	Ga	32	Ge	33	As	34	Se	35	Br	36	Kr
5		37	Rb	38	Sr	39	Y	40	Zr	41	Nb	42	Mo	43	Tc	44	Ru	45	Rh	46	Pd	47	Ag	48	Cd	49	In	50	Sn	51	Sb	52	Te	53	I	54	Xe
6		55	Cs	56	Ba	57	*La	72	Hf	73	Ta	74	W	75	Re	76	Os	77	Ir	78	Pt	79	Au	80	Hg	81	Tl	82	Pb	83	Bi	84	Po	85	At	86	Rn
7		87	Fr	88	Ra	89	+Ac	104	Rf	105	Ha	106	Sg	107	Ns	108	Hs	109	Mt	110	110	111	111	112	112	113											

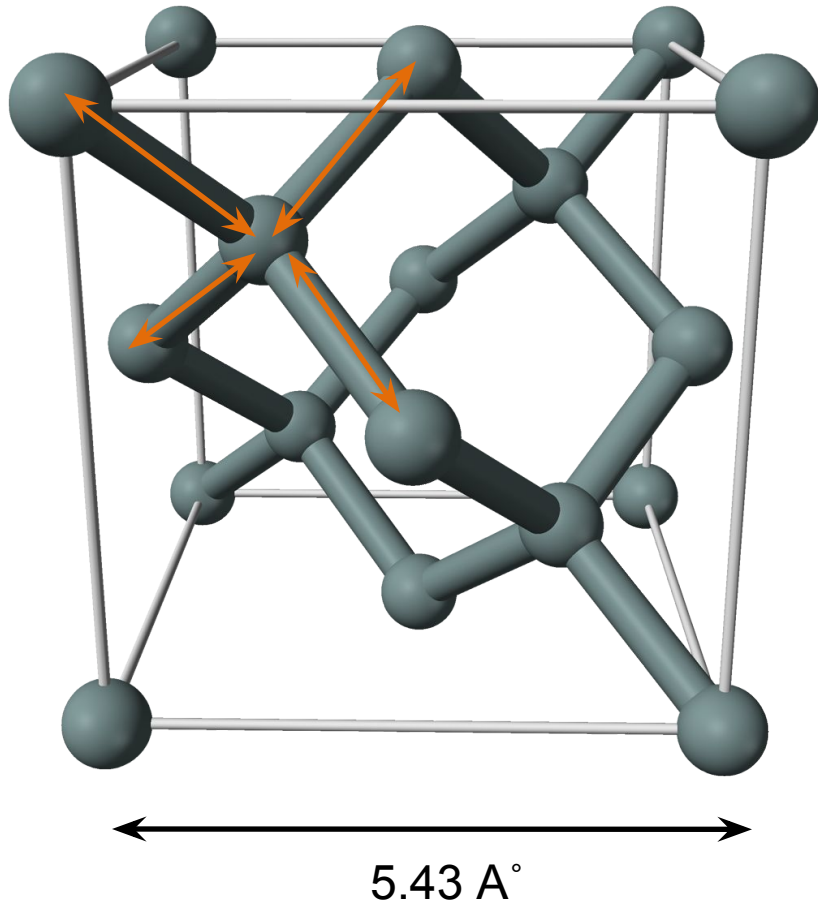
# Crystal Structure of Si

Often known as the diamond lattice

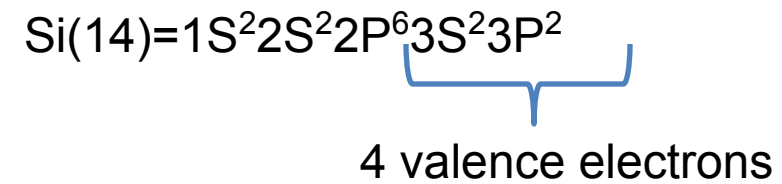


Transmission Electron Microscopy Image of Si taken at Lawrence Berkeley National Laboratory

# Crystal Structure of Si



Each atom has 4 nearest neighbors

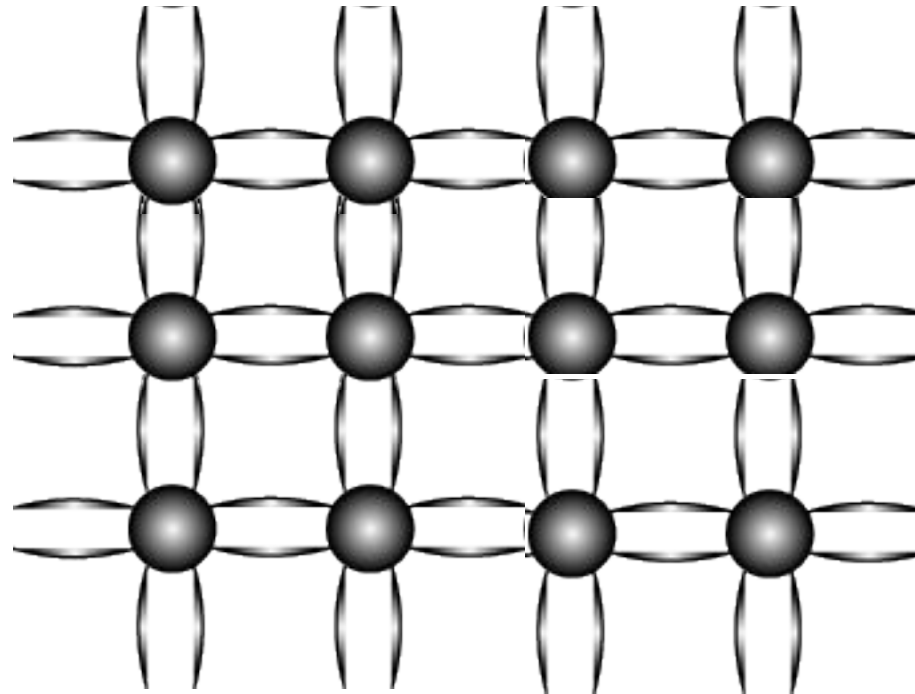


Each atom shares 2 electrons with 4 nearest neighbors to form a covalent bond

# The Bond Model

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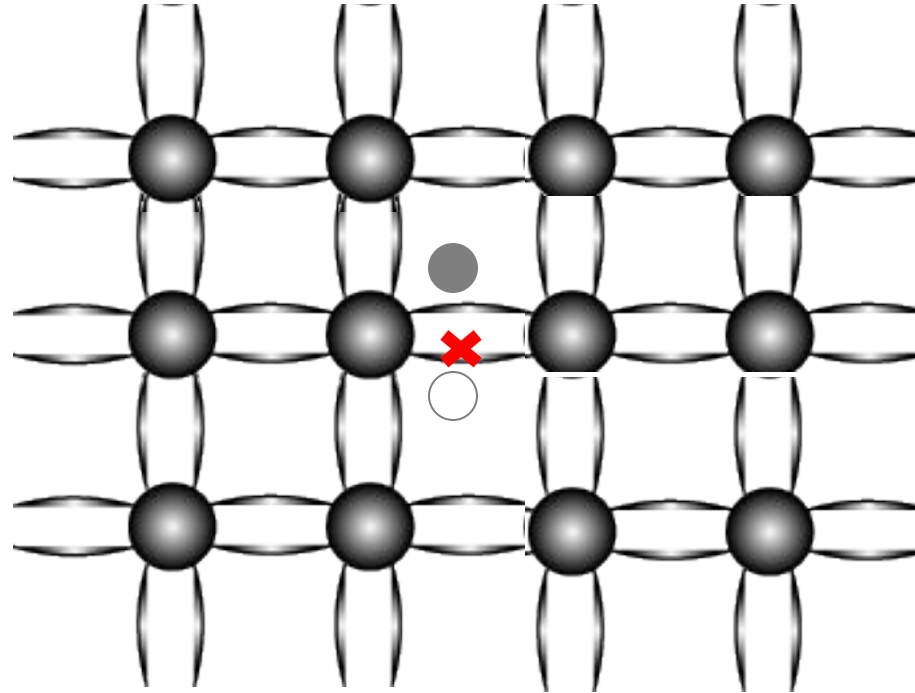
Each atom shares 2 electrons with 4 nearest neighbors to form a covalent bond



At  $T=0\text{K}$ , all bonds are satisfied, there are no **free** carriers, no current flows, looks like an insulator

# Intrinsic Si: The Bond Model: Electrons

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At finite temperature, an electron may gain enough energy to break the covalent bond, become **free** and move around.

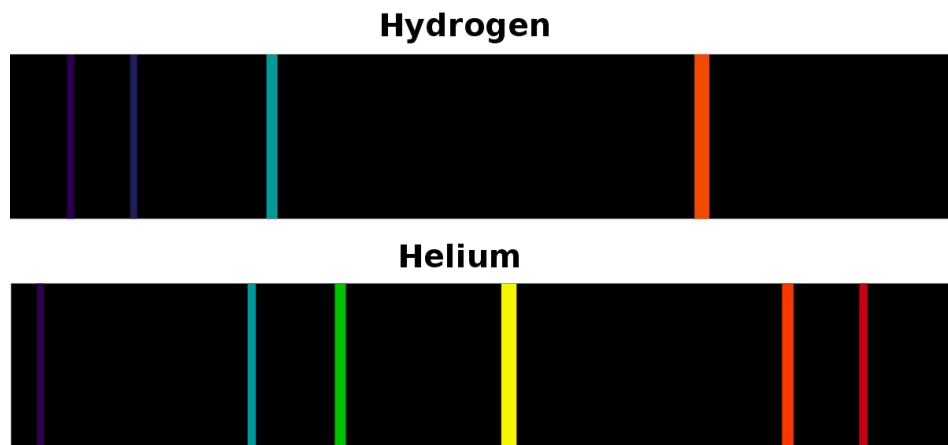


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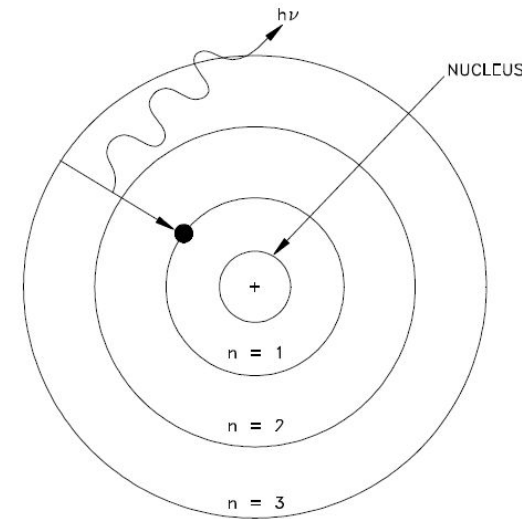
# Energy Band Model

# Electrons around nucleus

It was known from John Herschel's experiment in (1826) that heated gas emits a unique combination of colors



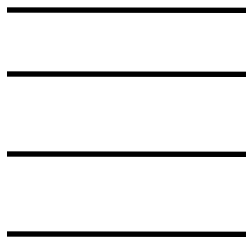
- In 1913 Niels Bohr proposed an atomic model that assumes electrons are orbiting around a positively charged nucleus in **specific shells**



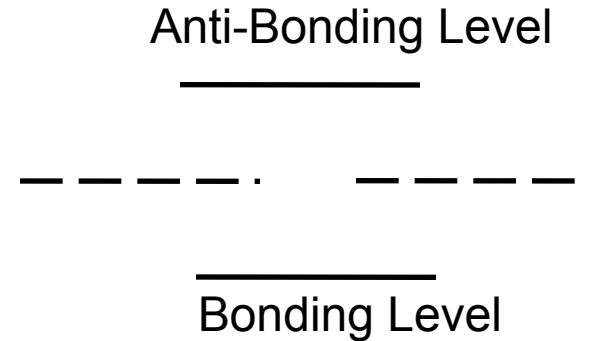
- When heated electrons can absorb the energy and go from shell 1 to 2. When cooling down, it comes down to 1, **emitting** the specific energy difference between 2 and 1 giving a specific color of light.

# Energy Levels and Formation of a Molecule

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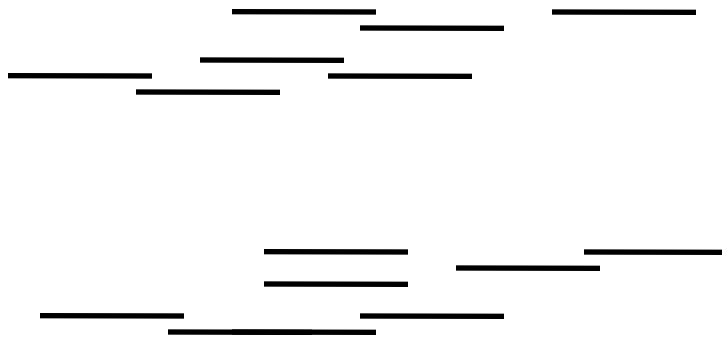
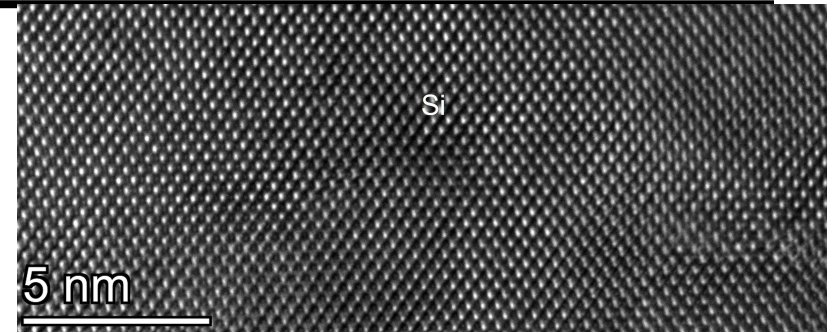
Discrete energy levels in an atom



When energy levels of two atoms interact, they create one bonding and one anti-bonding level

# Energy Bands

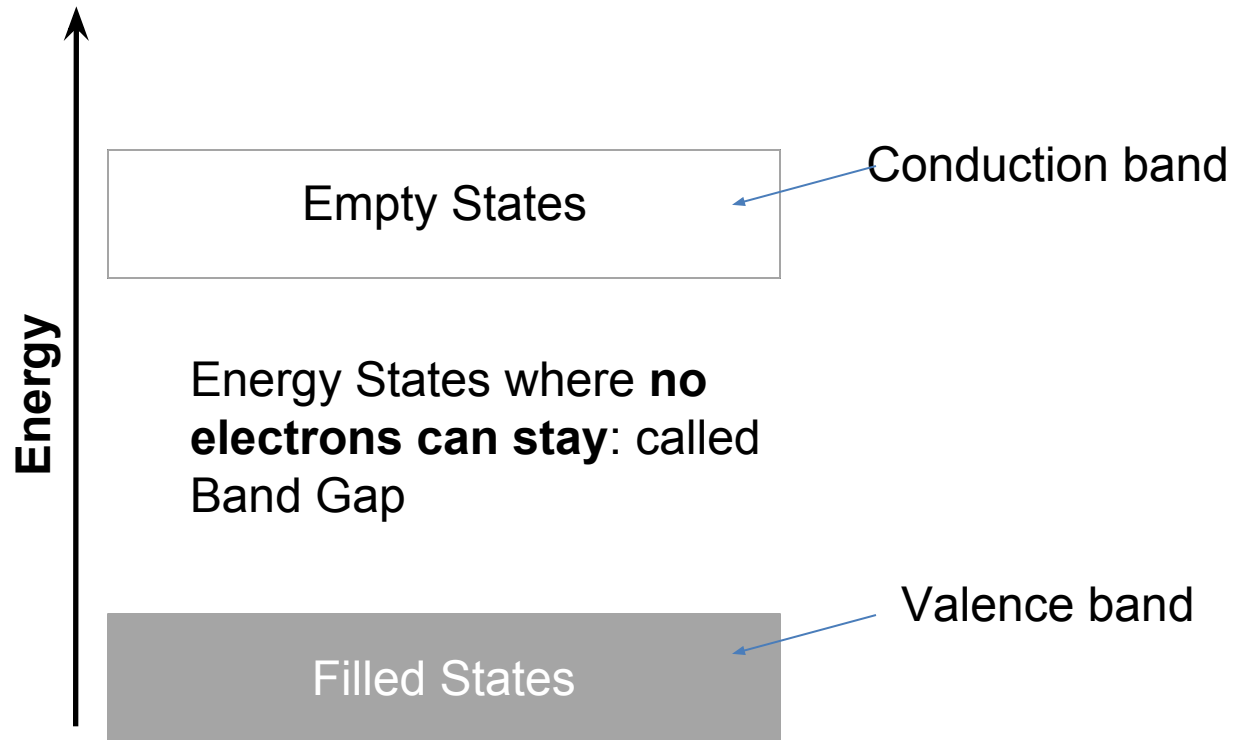
In a solid as many atoms are brought close to each other they create many many bonding and anti-bonding levels



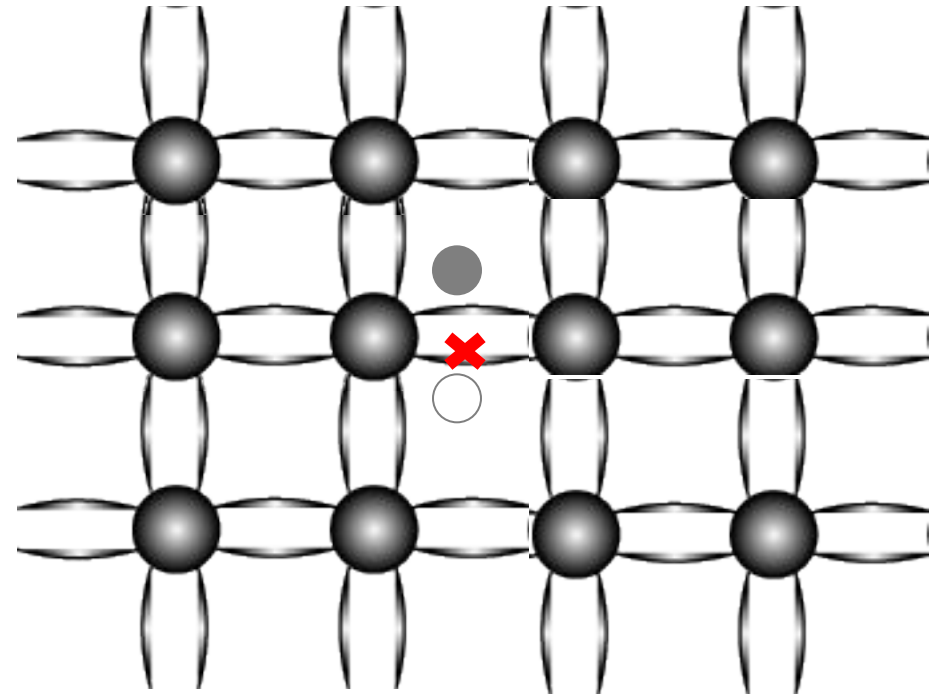
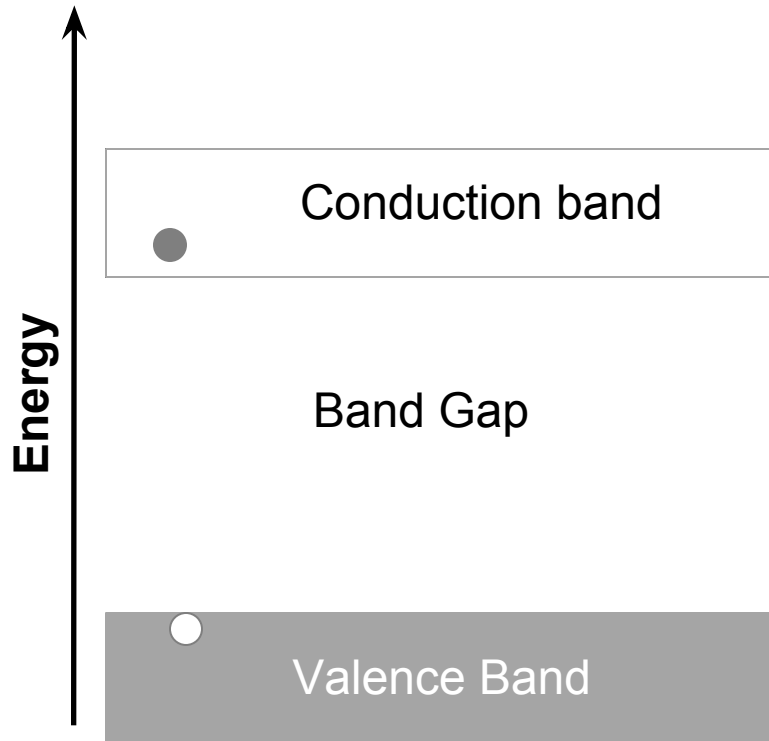
Energy Bands

# Energy Bands

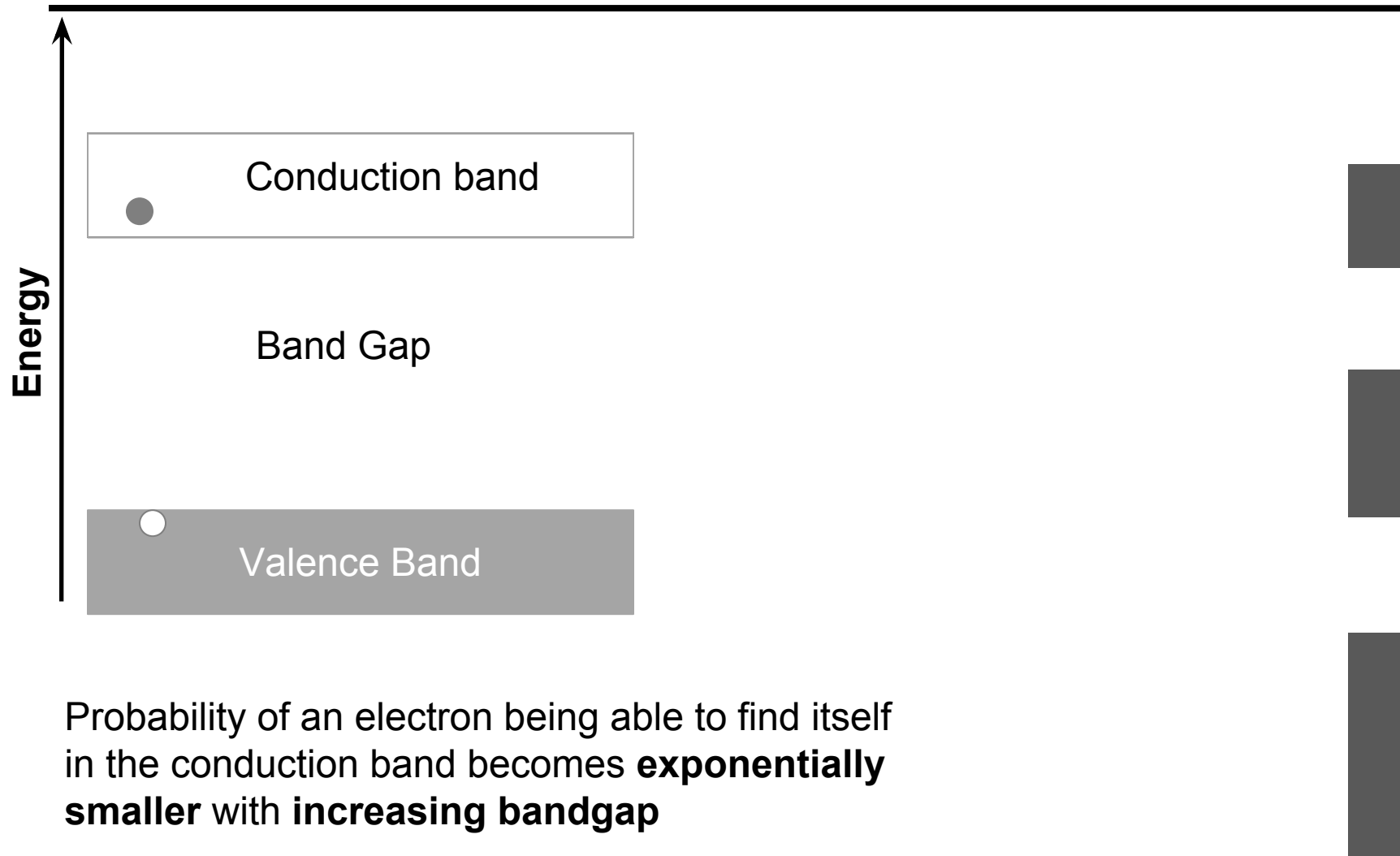
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# Energy Bands

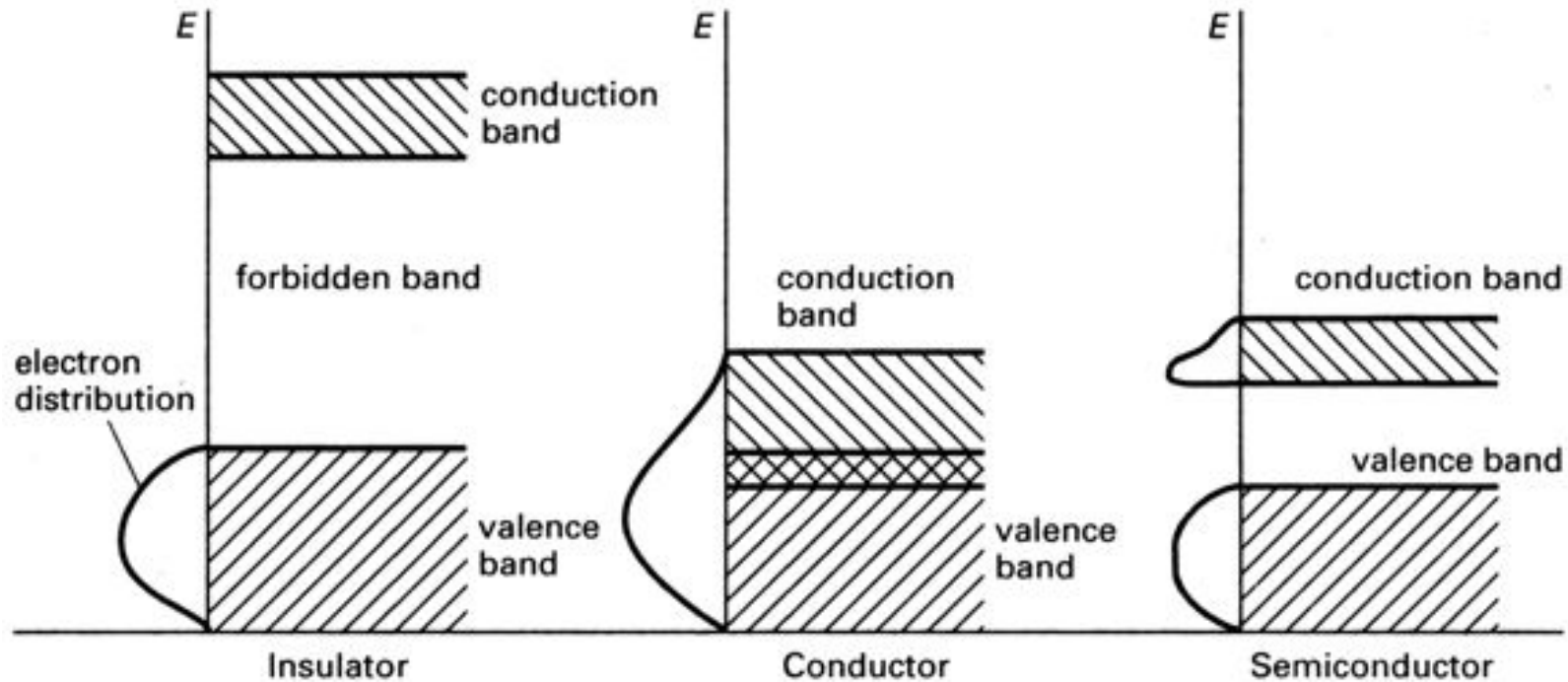


# Probability of an electron being free



Probability of an electron being able to find itself in the conduction band becomes **exponentially smaller** with **increasing bandgap**

# Semiconductors, Insulators and Conductors

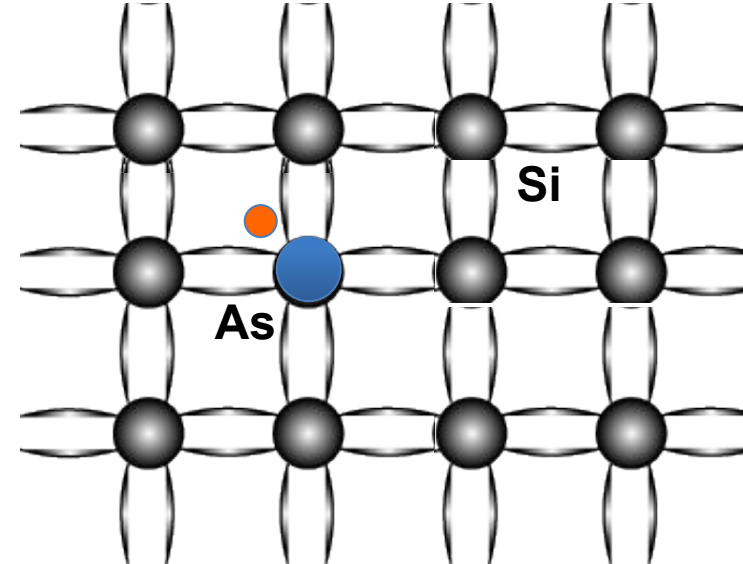
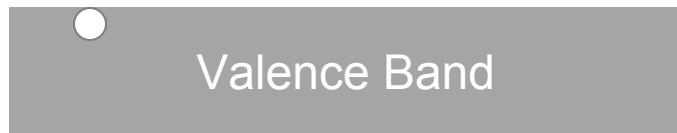
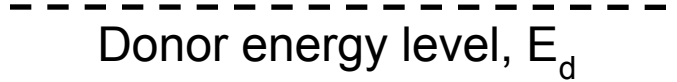
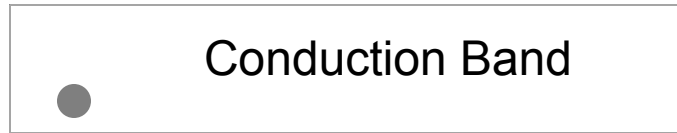


- ✓ Conductors have half filled bands
- ✓ Semiconductors have lower energy gap compared to insulators and can be doped



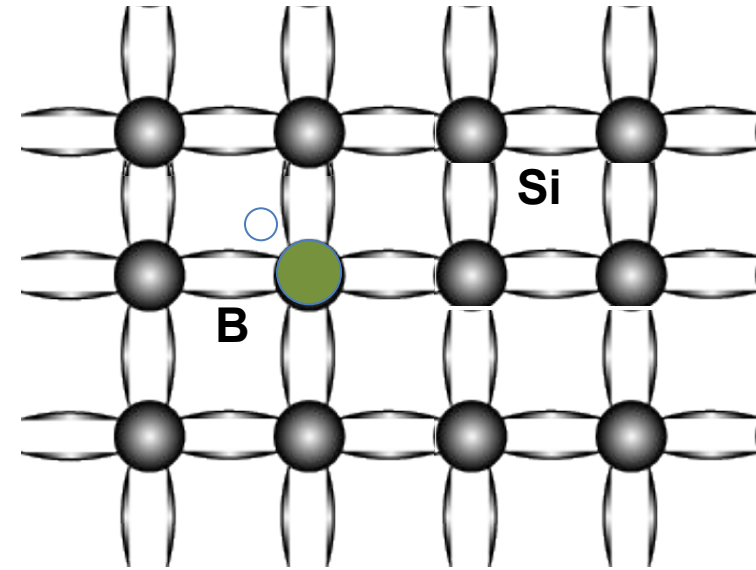
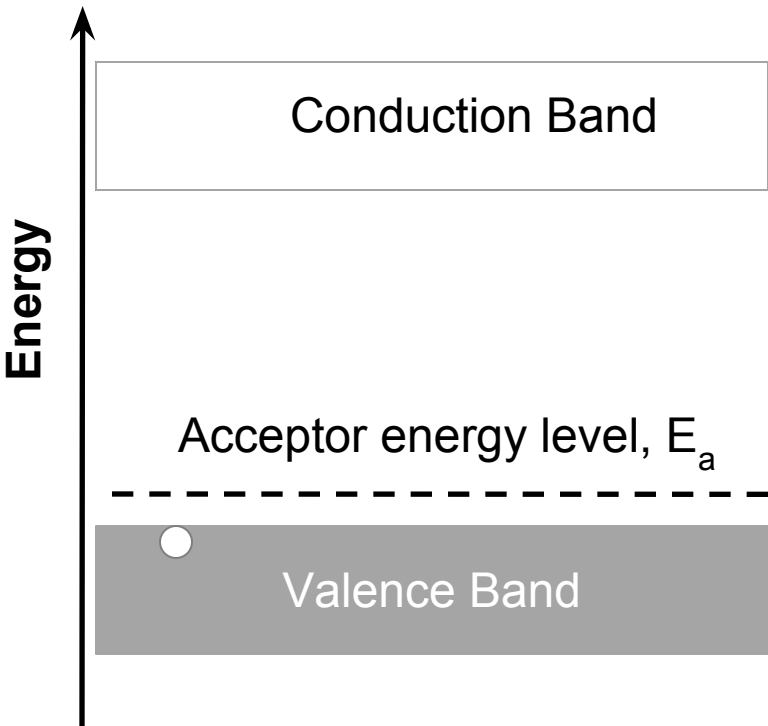
# Doping

Energy



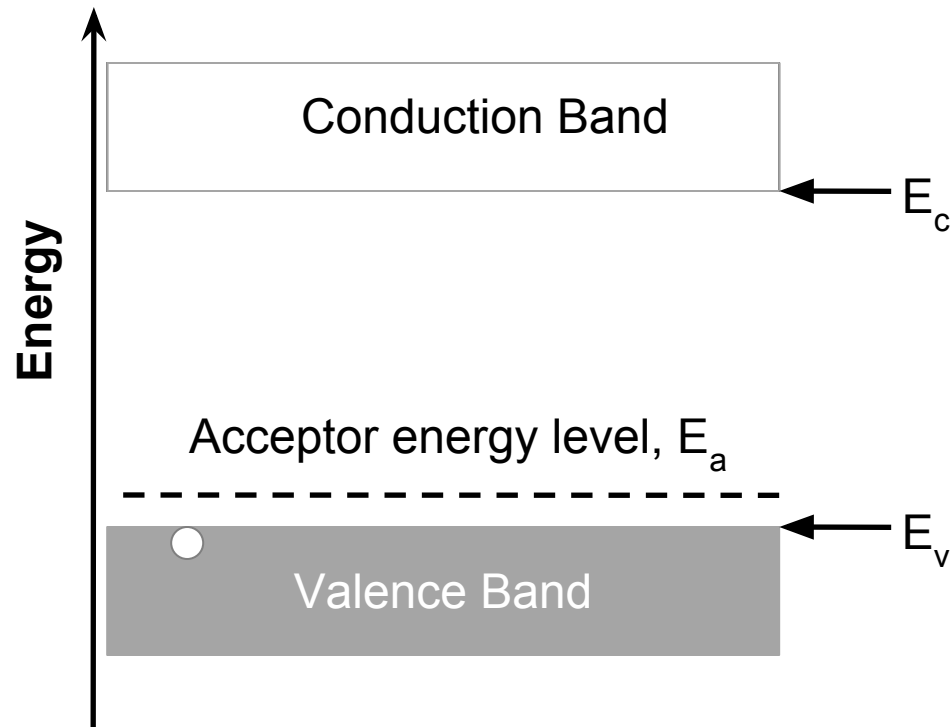
	III	IV	V	
	Boron (B)	Carbon (C)		
...	Aluminum (Al)	Silicon (Si)	Phosphorous (P)	...
	Galium (Al)	Germanium (Ge)	Arsenic (As)	
		⋮		

# Doping



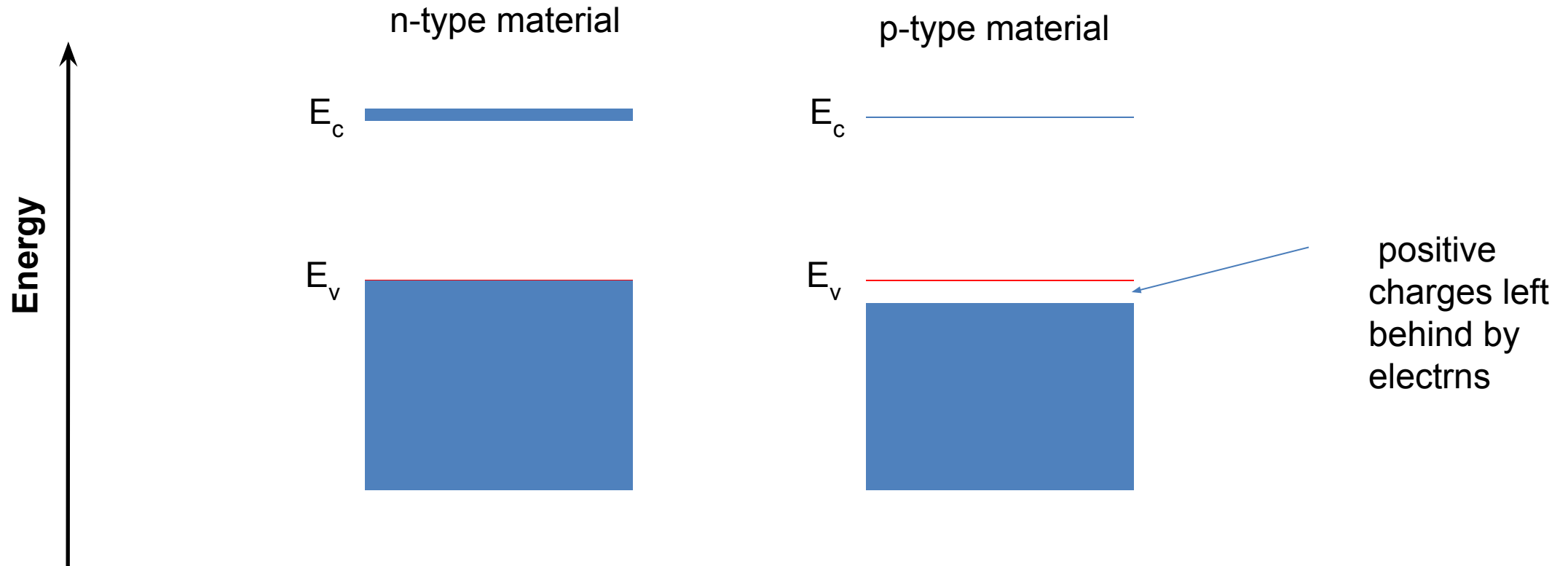
	III	IV	V	
	Boron (B)	Carbon (C)		
...	Aluminum (Al)	Silicon (Si)	Phosphorous (P)	...
	Galium (Al)	Germanium (Ge)	Arsenic (As)	
		⋮		

# A convention about energy bands



Only the edge of the bands are shown where the difference between the two edges is the bandgap

# N and P type Materials, Junctions and Devices



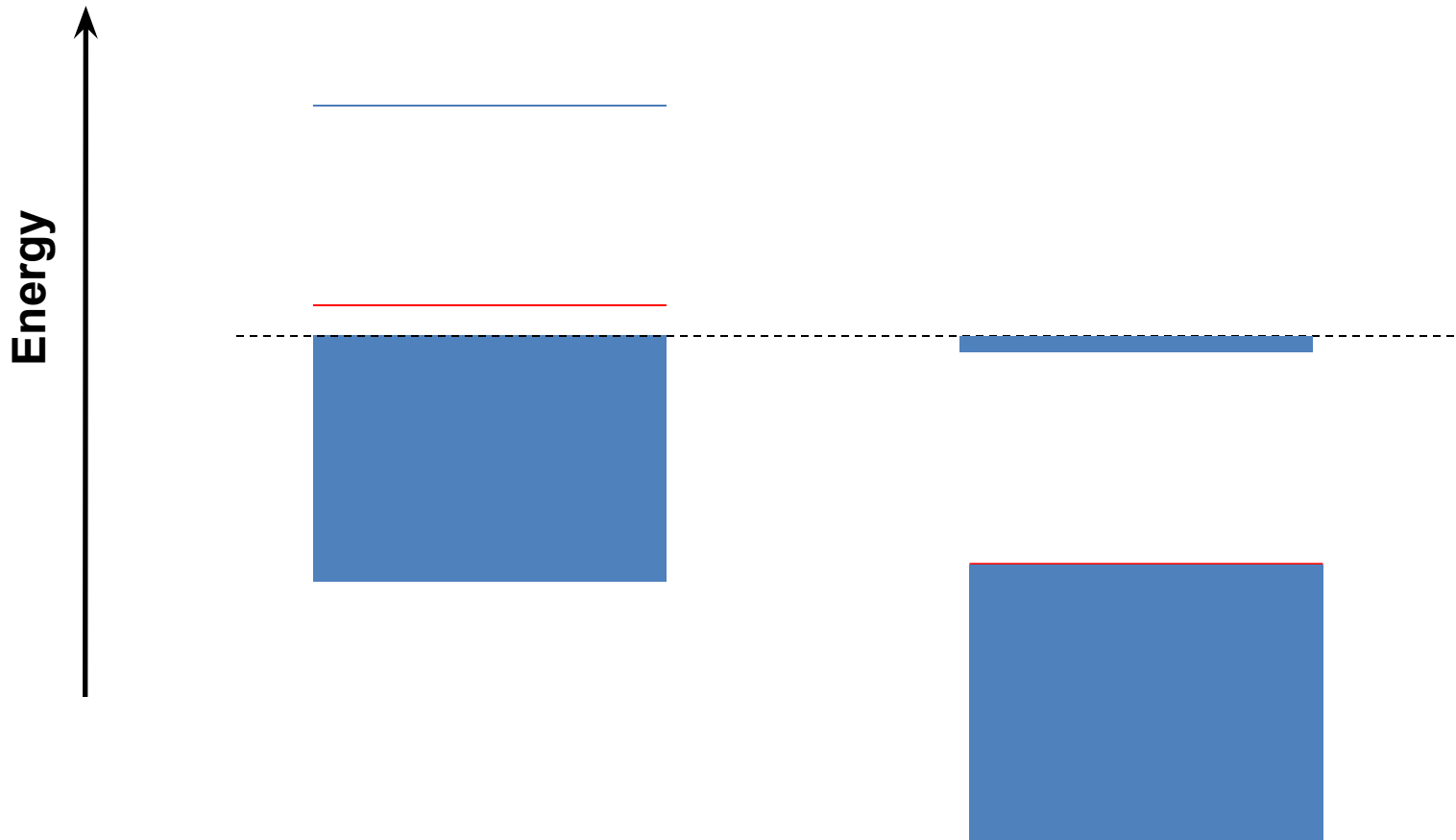
\*Blue color indicates electrons

# Combining N and P materials

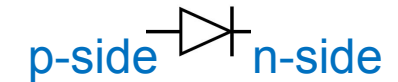
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# N and P type Materials, Junctions and Devices

## Qualitative Picture of a Junction Formation



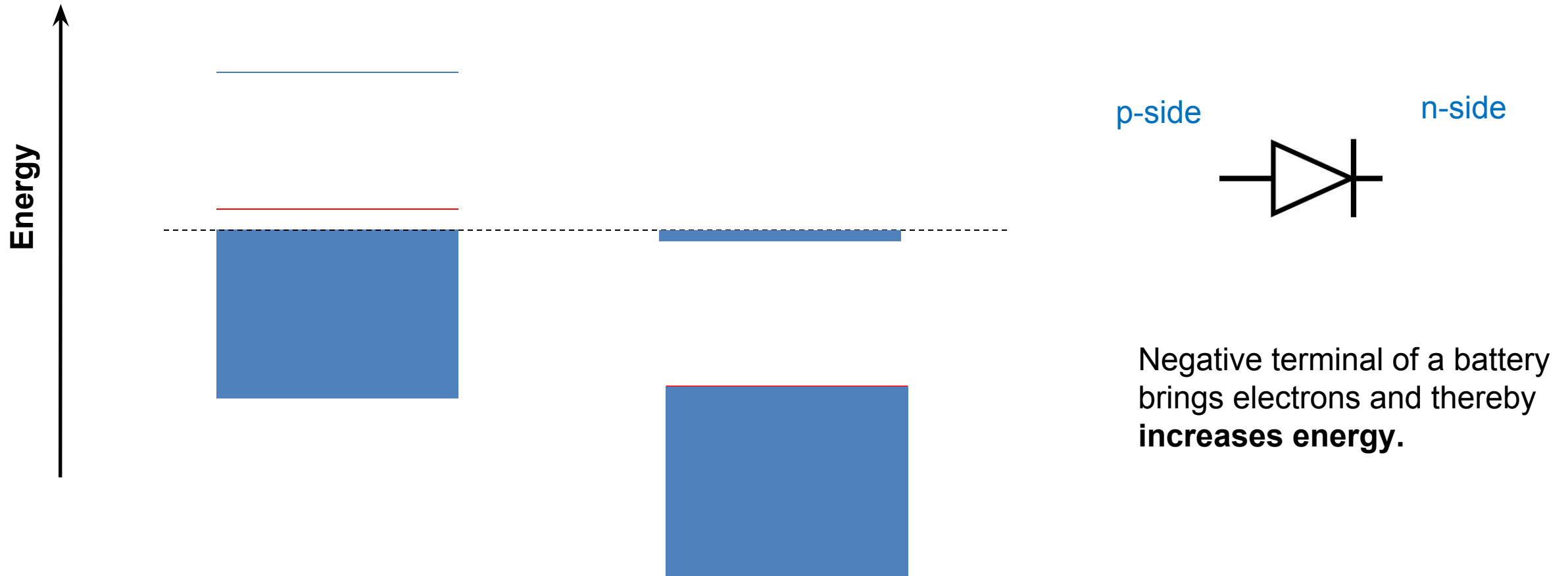
- When a n and p are put together, they form a p-n junction diode  
Symbol:



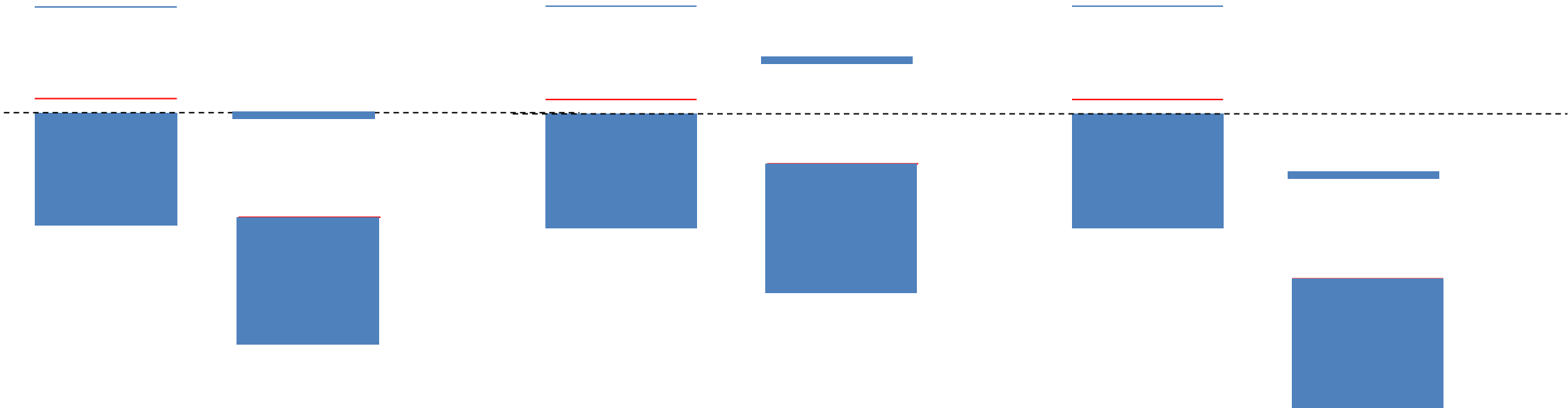
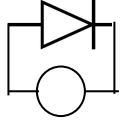
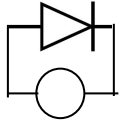
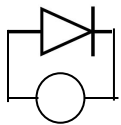
- Electron densities align in energy so that there is no difference in concentration
- Technically what aligns is the energy level where probability of finding an electron is  $\frac{1}{2}$  □ to be discussed in more details in EE130

# What does a voltage do?

Qualitative Picture of a Junction Formation



# N and P type Materials, Junctions and Devices

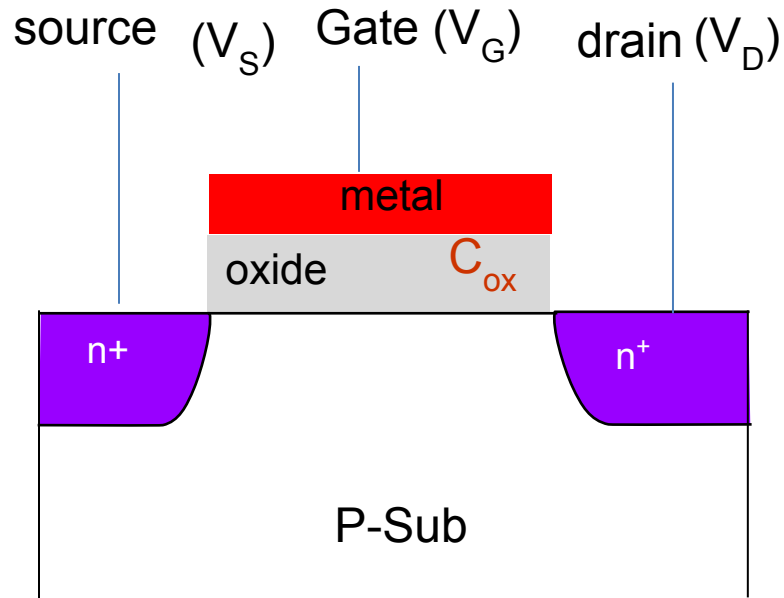




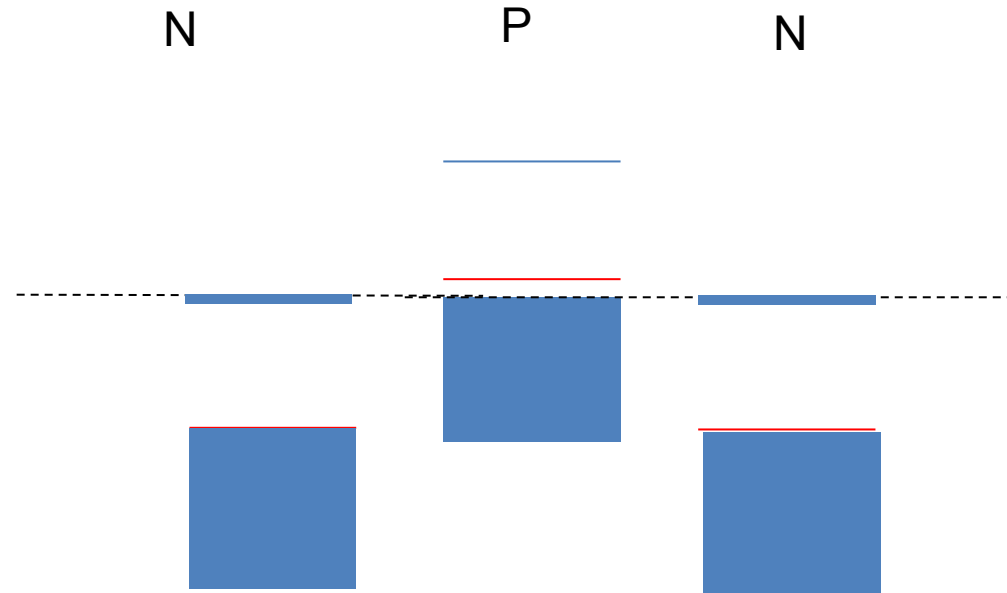
# I-V of a PN junction Diode

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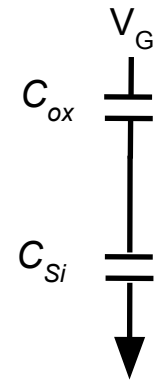
# Metal-Oxide-Semiconductor Field Effect Transistor (MOSFET)



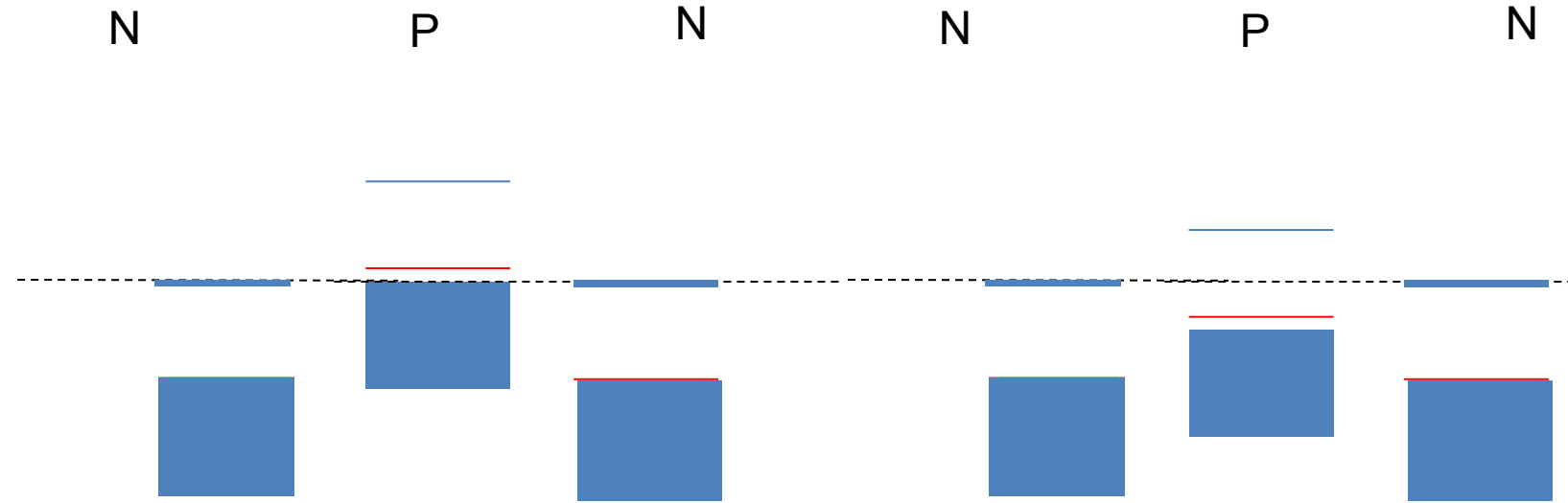
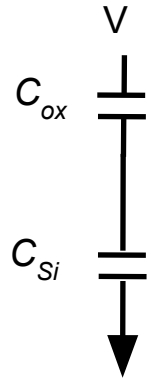
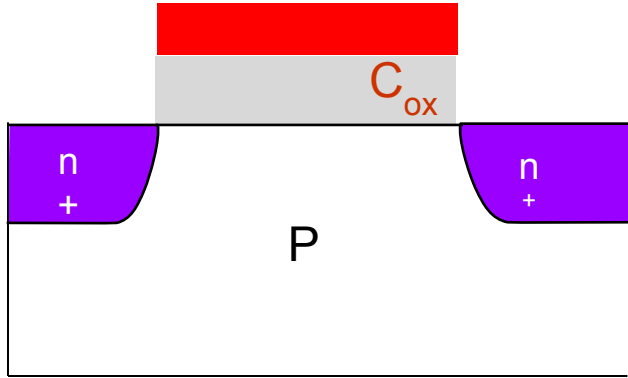
- + or – in the name of n or p type material indicates extent of doping. N+ means doped **heavily** to n type.
- In common MOSFET source and drain voltages are interchangeable



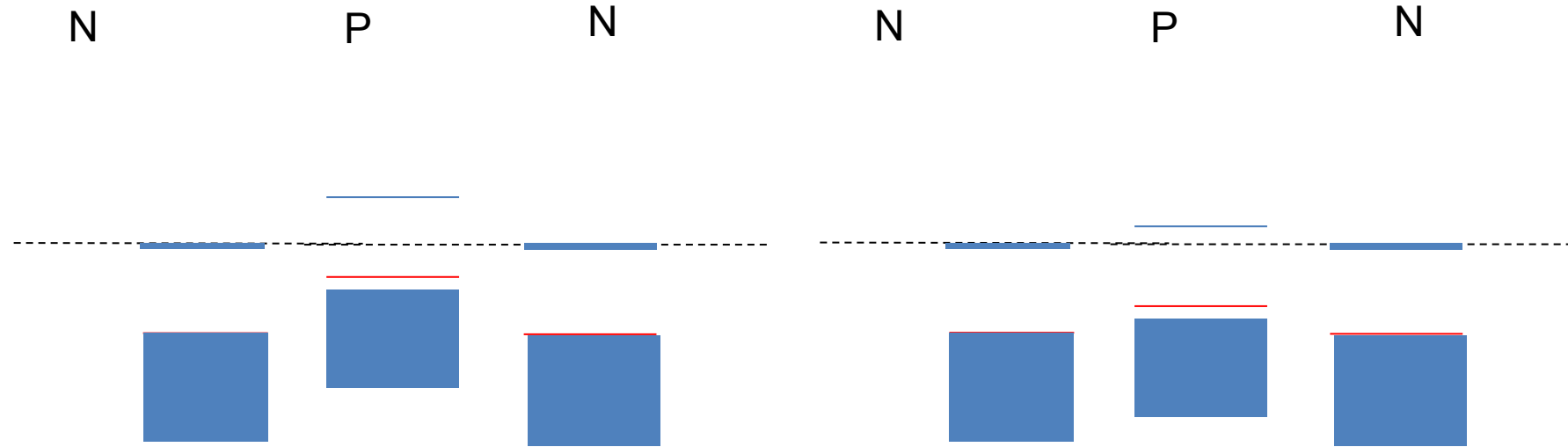
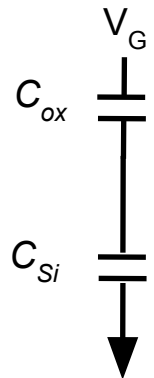
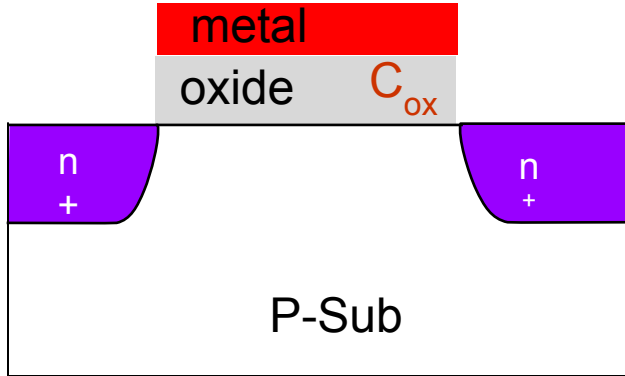
P-type semiconductor in the middle with little to no electrons on the conduction band acts like an insulator



# MOSFET

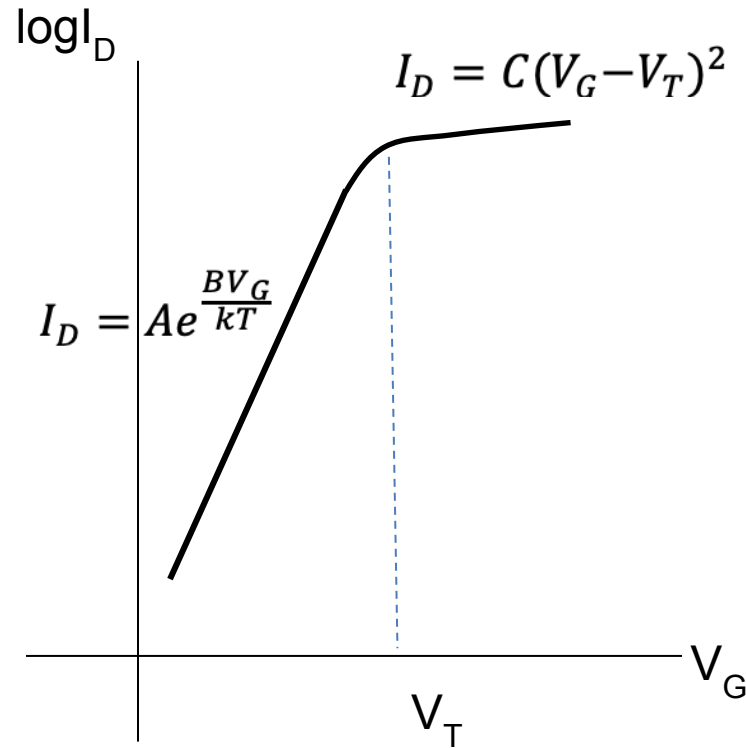
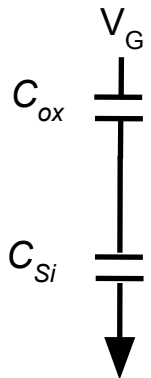
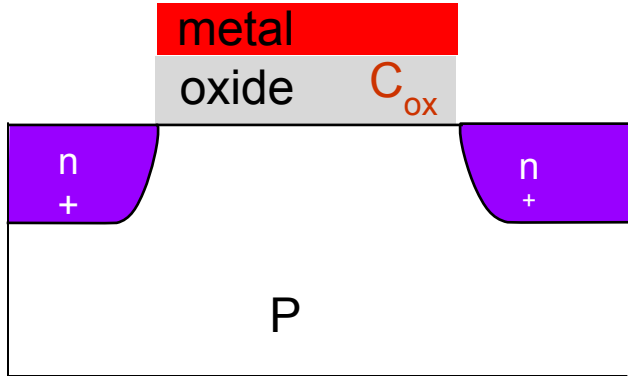


# MOSFET

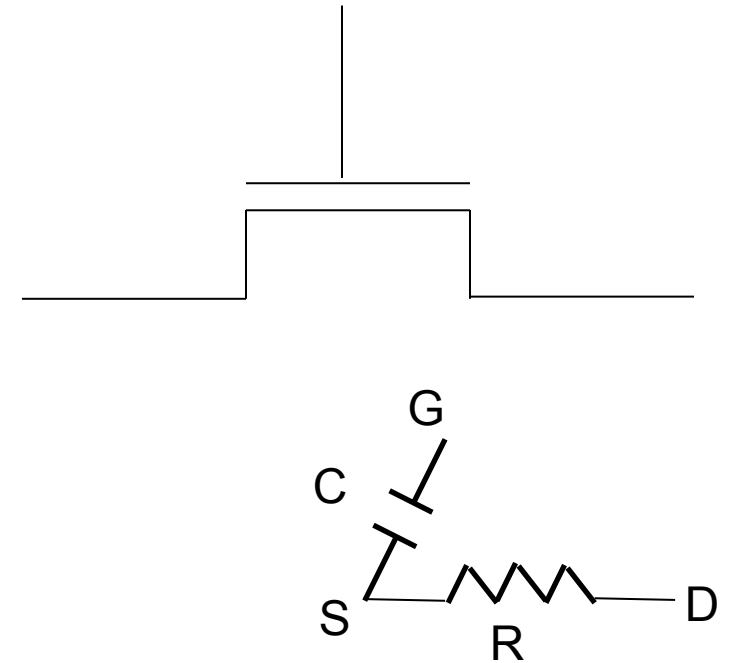


At large gate voltages, one reaches close to maximum charge density achievable in Si. So rate of change in increase in electron density with gate voltage slows down

# MOSFETs



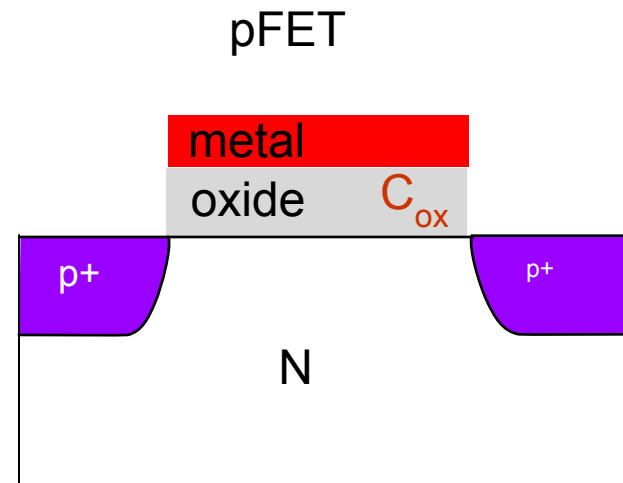
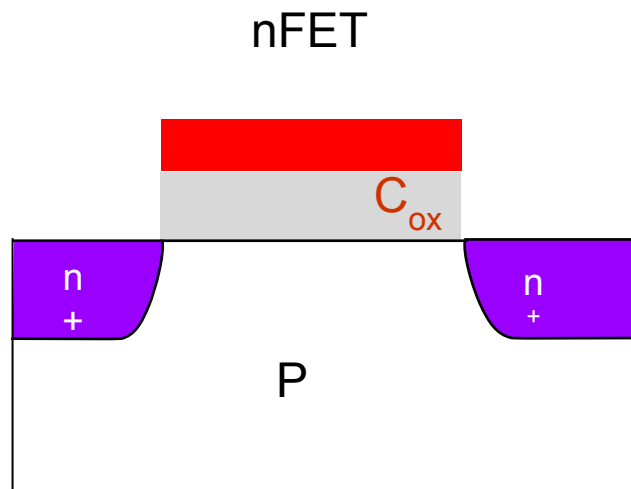
Assuming large  $V_{DS}$  is present



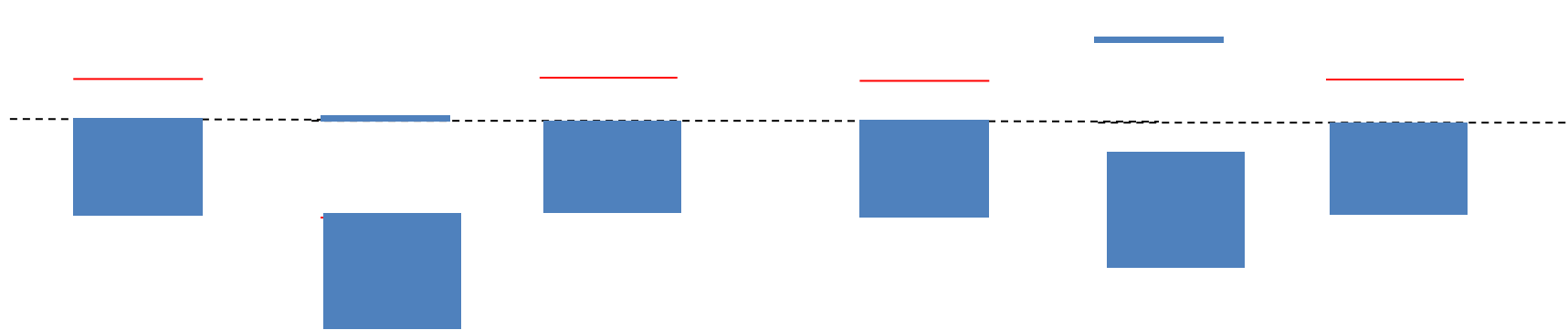
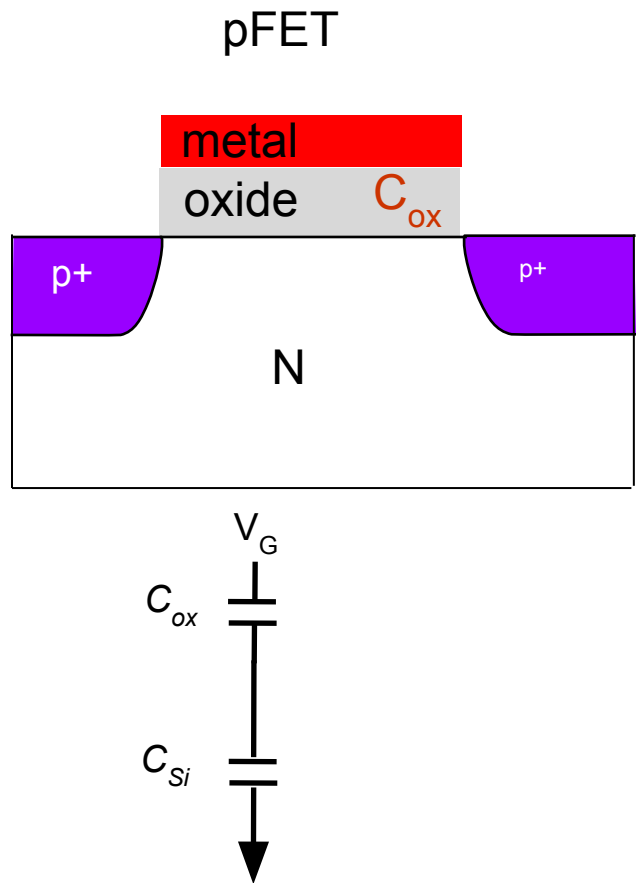
- C is the series combination of  $C_{ox}$  and  $C_{si}$
- $R = I_{DS} / V_{DS}$

# nFET vs pFET

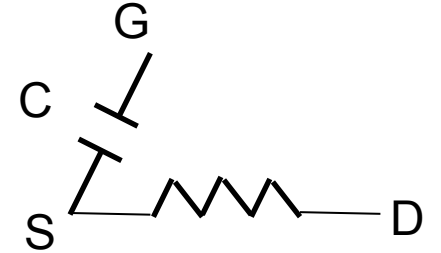
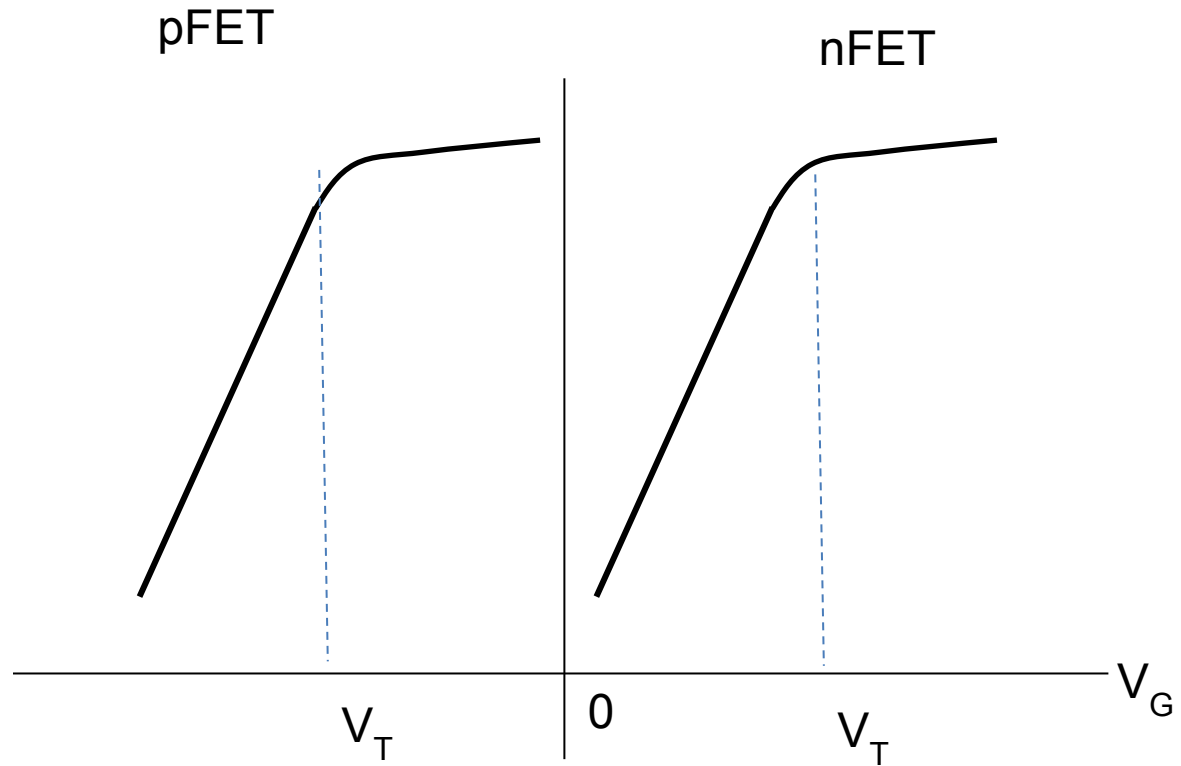
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# nFET vs pFET



# nFET vs pFET

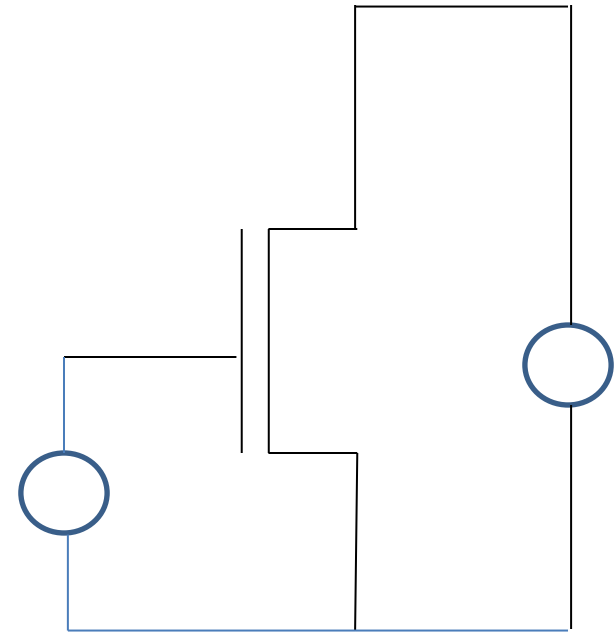


- nFET,  $V_{GS}$  and  $V_T$  are positive
- pFET,  $V_{GS}$  and  $V_T$  are negative



# FET as an analog amplifier

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When  $V_{GS} < V_T$

$$I_D = Ae^{\frac{BV_G}{kT}}$$

Small change in  $V_{GS}$  changes  $I_D$  exponentially

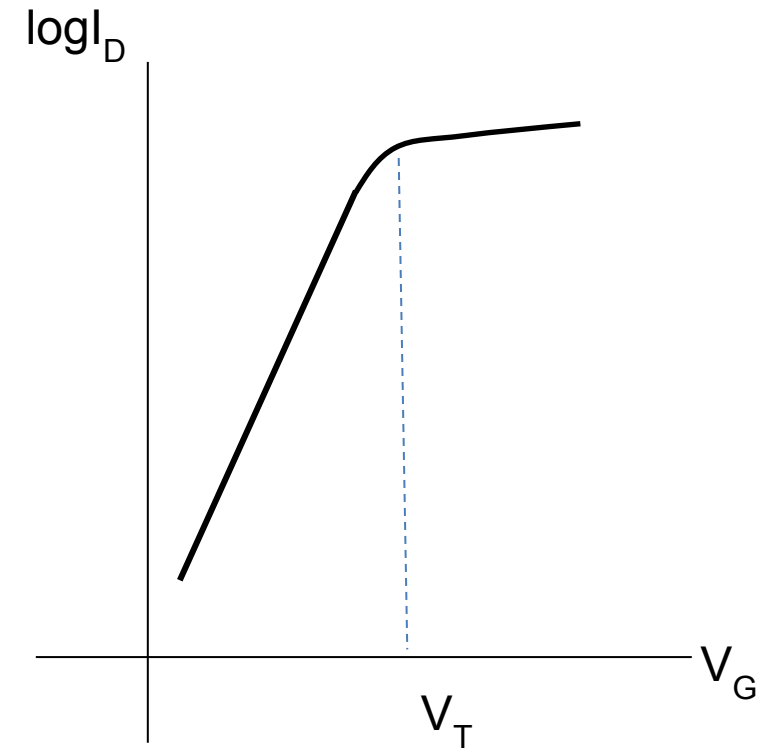
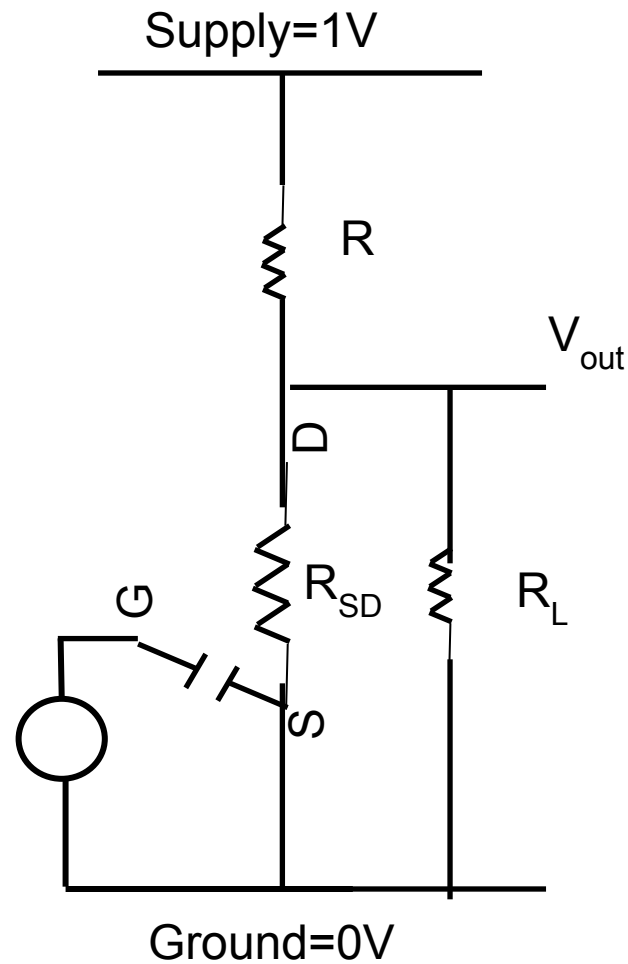
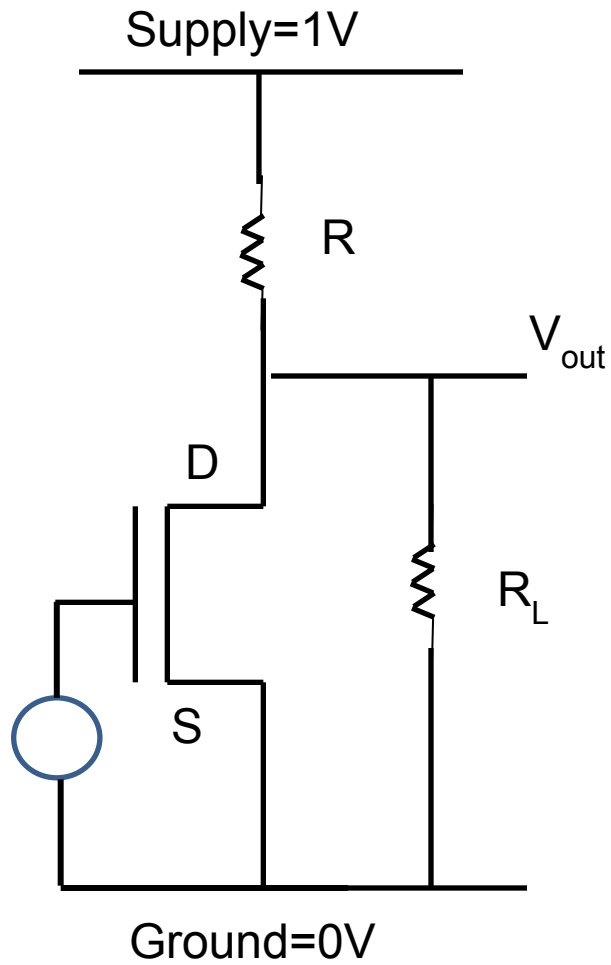
When  $V_{GS} > V_T$

$$I_D = C(V_G - V_T)^2$$

Small change in  $V_{GS}$  changes  $I_D$  quadratically

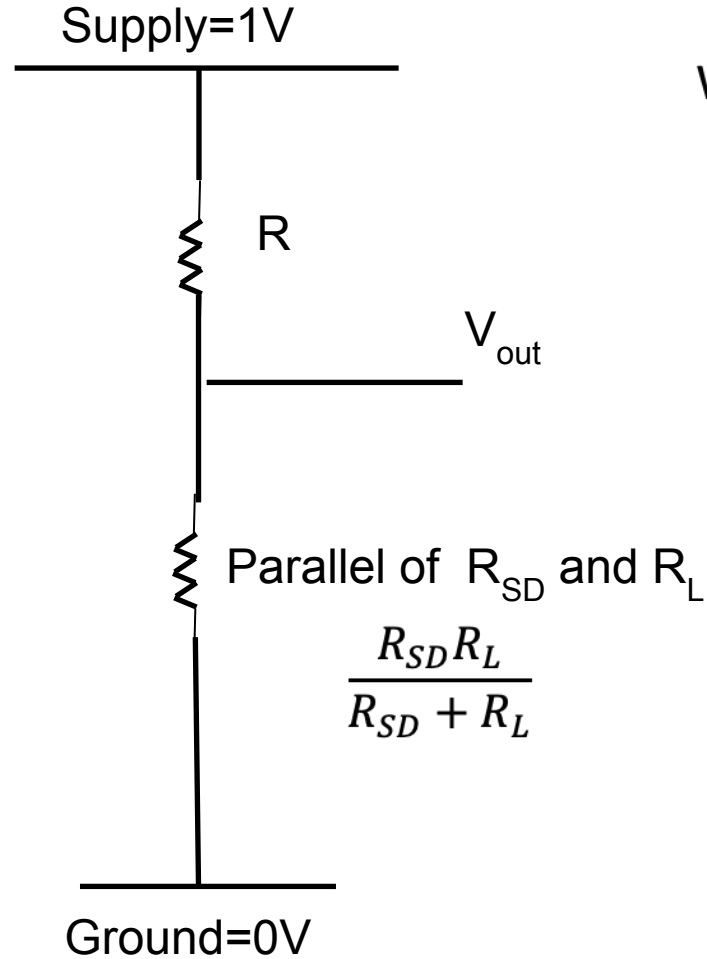
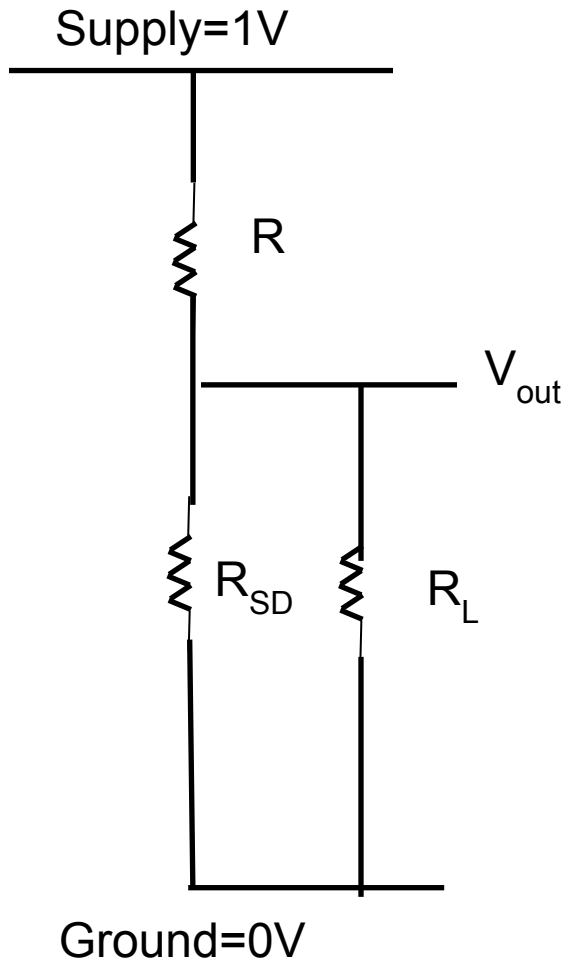
Overall, Large changes in the Drain current can be achieved by changing Gate Voltage

# FET in digital logic



When  $V_{GS}$  is High,  $R_{SD}$  is low  
When  $V_{GS}$  is Low,  $R_{SD}$  is High

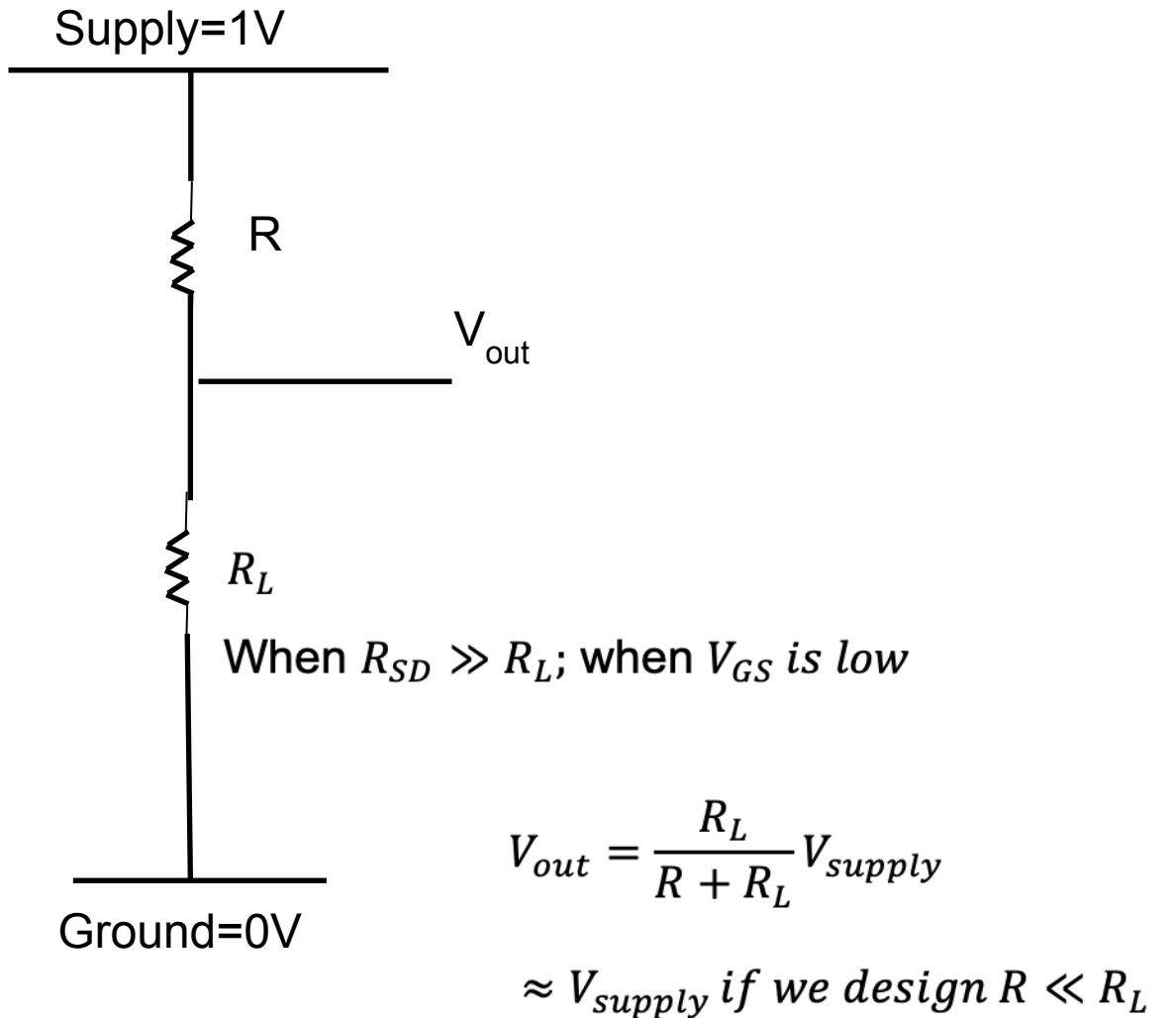
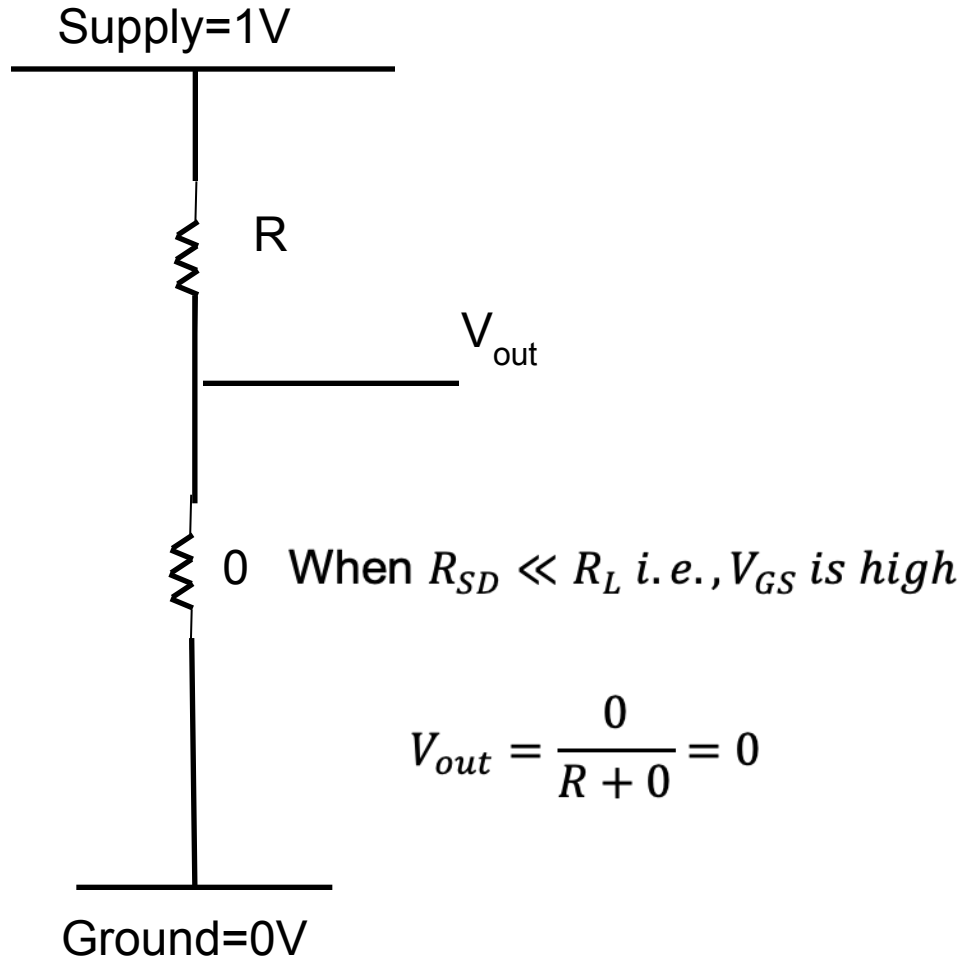
# FET in digital logic



When  $R_{SD} \ll R_L$ ;  $\frac{R_{SD}R_L}{R_{SD} + R_L} \approx \frac{R_{SD}}{R_L} \approx 0$

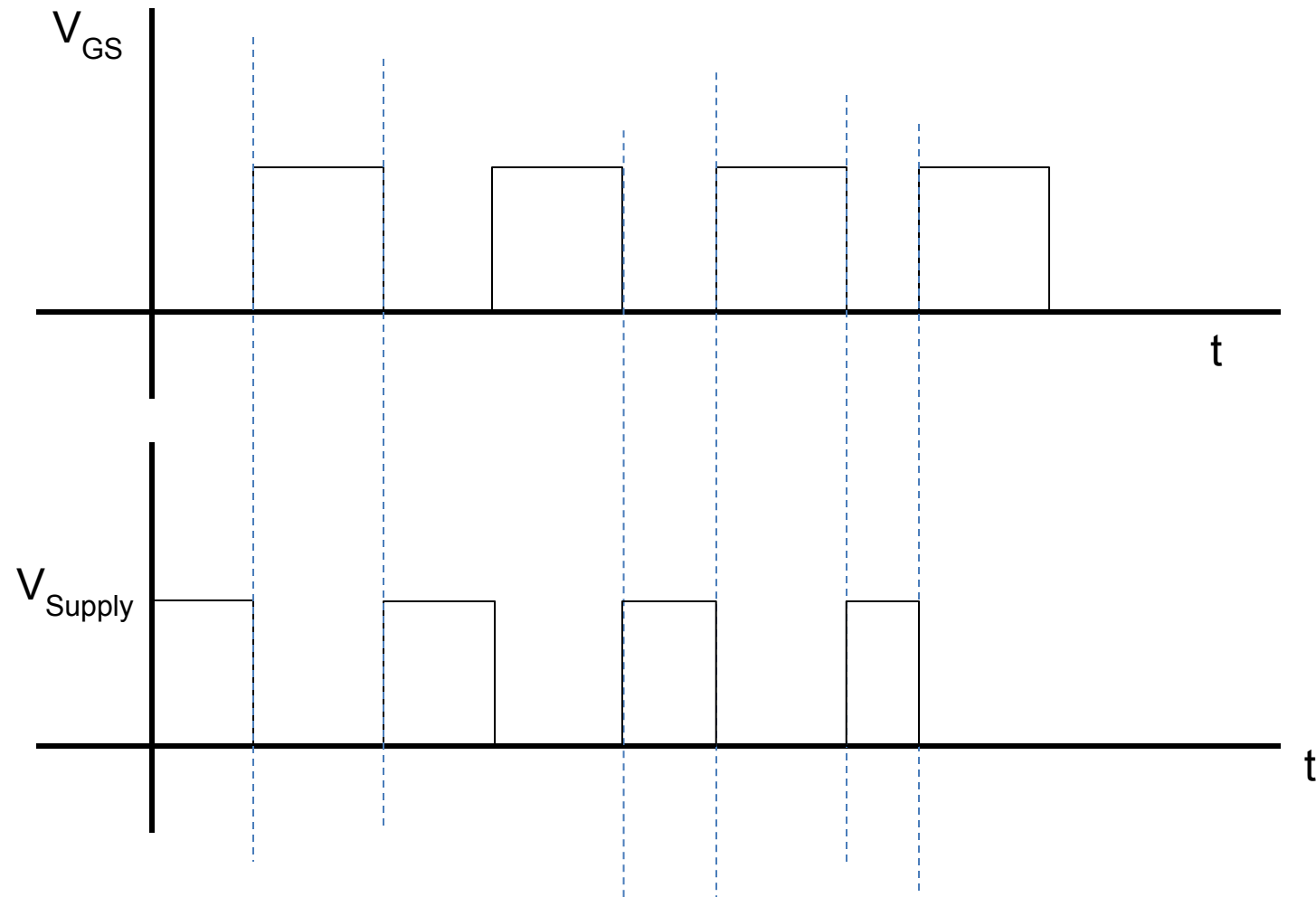
When  $R_{SD} \gg R_L$ ;  $\frac{R_{SD}R_L}{R_{SD} + R_L} \approx R_L$

# FET in digital logic

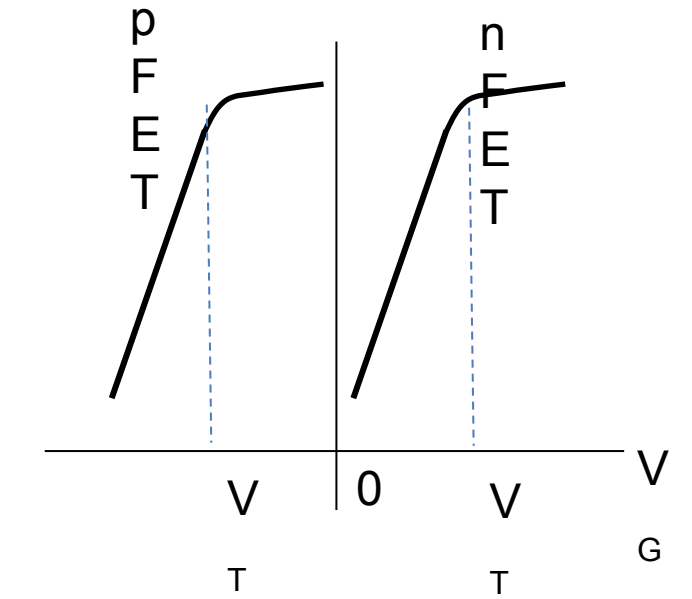
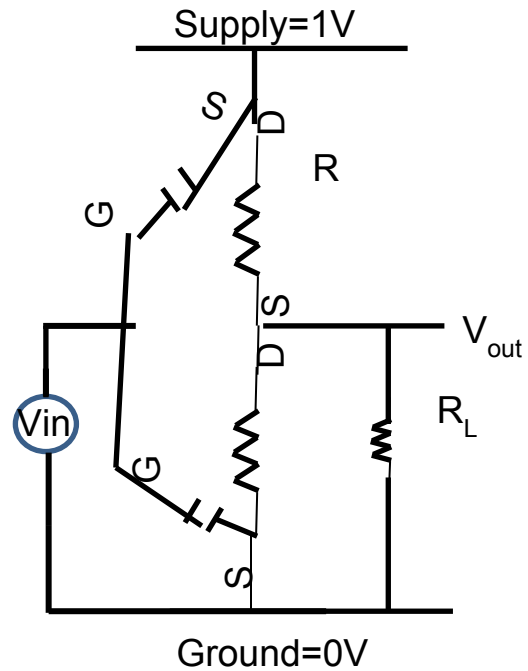
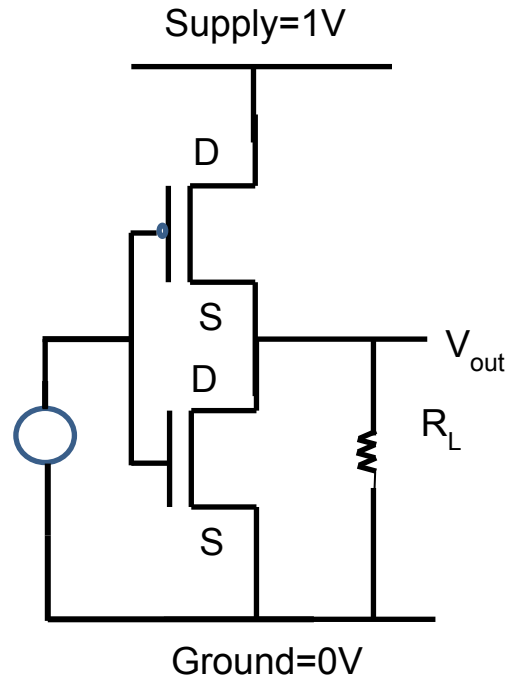
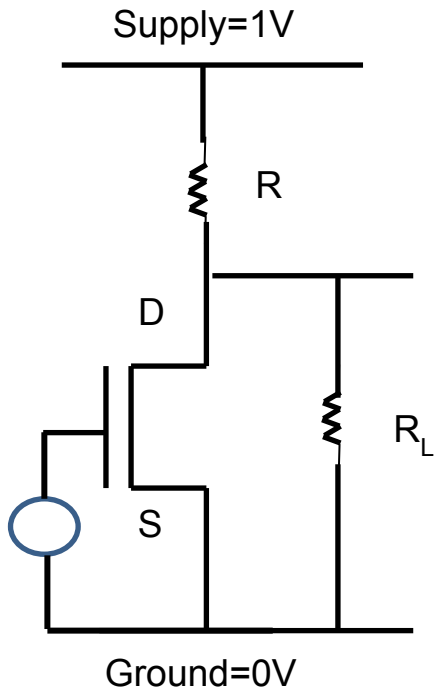


# FET in digital logic

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# CMOS



**$V_{in}=1V$**

$V_{GS}$  for nFET is HIGH  $\square$   $R_{SD}$  is LOW

$V_{GS}$  for pFET is LOW  $\square$   $R_{SD}$  is high

**$V_{in}=0V$**

$V_{GS}$  for nFET is LOW  $\square$   $R_{SD}$  is HIGH

$V_{GS}$  for pFET is HIGH **NEGATIVE**  $\square$   $R_{SD}$  is LOW